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	Application No.	Applicant(s)	7
	10/067,309	ITO, HIROSHI	
Notice of Allowability	Examiner	Art Unit	
	Edna Wong	1753	
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED) or other appropriate comr RIGHTS. This application is	in this application. If not included nunication will be mailed in due co	urse. THIS
1. 🖾 This communication is responsive to Amendment After Fit	nal June 8, 2004.		
2. ☑ The allowed claim(s) is/are <u>1-10</u> .			
3. \boxtimes The drawings filed on <u>07 February 2002</u> are accepted by the second sec	the Examiner.		
 4. Acknowledgment is made of a claim for foreign priority u a) All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)). * Certified copies not received:	e been received. e been received in Applicat	ion No	n from the
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDON! THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		le a reply complying with the requ	irements
5. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which giv			TICE OF
6. CORRECTED DRAWINGS (as "replacement sheets") mu	st be submitted.		
(a) ☐ including changes required by the Notice of Draftsper		ew (PTO-948) attached	
1) ☐ hereto or 2) ☐ to Paper No./Mail Date	<u>-</u> ·		
(b) ☐ including changes required by the attached Examiner Paper No./Mail Date	's Amendment / Comment	or in the Office action of	
Identifying indicia such as the application number (see 37 CFR each sheet, Replacement sheet(s) should be labeled as such in			ack) of
7. DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT			te the
Attachment(s)			
1. Notice of References Cited (PTO-892)	5. Notice of	Informal Patent Application (PTO-	152)
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	Paper No	 Interview Summary (PTO-413), Paper No./Mail Date <u>June 24, 2004</u>. Examiner's Amendment/Comment 	
 Information Disclosure Statements (PTO-1449 or PTO/SB/ Paper No./Mail Date 	· 		
4. Examiner's Comment Regarding Requirement for Deposit		's Statement of Reasons for Allow	ance
of Biological Material	9.	EDNA WONG PRIMARY EXAM	MER

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Eckhard H. Kuesters on June 24, 2004.

The application has been amended as follows:

IN THE CLAIMS

Claims 11-20 have been cancelled.

REASONS FOR ALLOWANCE

The following is an examiner's statement of reasons for allowance:

Claims 1-9 are allowable over the prior art of record because the prior art does not teach or suggest a laser processing method for irradiating a mask with a plurality of openings formed therein with a pulsed laser, and irradiating a plurality of portions of a work to be processed with said pulse laser transmitted through said plurality of openings at the same time, said method comprising the steps of moving and setting as presently claimed, esp., wherein respective laser irradiated regions disposed adjacent to one another on said work are formed by irradiation with said pulse laser transmitted through said openings formed in positions different from one another on said mask, and

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boundaries of said laser irradiated regions disposed adjacent to each other contact at least each other.

Claim 10 is allowable over the prior art of record because the prior art does not teach or suggest a laser processing method for irradiating a mask with a plurality of linear openings formed therein with a pulse laser, and irradiating a plurality of portions of a silicon film with said pulse laser transmitted through said plurality of openings at the same time, said method comprising the steps of allowing, moving, setting and polycrystallizing as presently claimed, esp., the step of setting the laser irradiated regions such that boundaries of said laser irradiated regions disposed adjacent to each other contact each other.

The prior art does not contain any language that teaches or suggests the above.

Im et al. do not teach moving said mask and said work with respect to each other.

Shoemaker et al. teach moving said mask and said work with respect to each other and emitting said pulse laser a plurality of times (page 4, ¶ [0044] and [0048]; and Figs. 2 and 3). Shoemaker et al. does not teach wherein boundaries of said laser irradiated regions disposed adjacent to each other contact at least each other.

Lau et al. teach moving said mask and said work with respect to each other and emitting said pulse laser a plurality of times (page 3, ¶ [0039] and [0044]; and Figs. 3-5). Lau et al. do not teach wherein boundaries of said laser irradiated regions disposed adjacent to each other contact at least each other.

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Hamada et al. teach moving said mask and said work with respect to each other and emitting said pulse laser a plurality of times (page 1, \P [0006]; and Fig. 1). Hamada et al. do not teach wherein boundaries of said laser irradiated regions disposed adjacent to each other contact at least each other.

Shoemaker et al., and Hamada et al. teach laser-drilling holes. Openings are formed in positions different from one another on a mask, however, the boundaries of the laser irradiated regions (= holes) disposed adjacent to each other are not taught to contact at least each other.

Lau et al. teach laser printing. Openings are formed in positions different from one another on a mask (letters "A", "B", "C", etc. in the laminated mask 1) [Fig. 1], however, the boundaries of said laser irradiated regions disposed adjacent to each other are not taught to contact at least each other.

Therefore, a person skilled in the art would not have been motivated to adopt the above conditions, and a prima facie case of obviousness cannot be established.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Edna Wong whose telephone number is (571) 272-

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1349. The examiner can normally be reached on Mon-Fri 7:30 am to 5:00 pm, alt.

Fridays off.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Nam Nguyen can be reached on (571) 272-1342. The fax phone number

for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the

Patent Application Information Retrieval (PAIR) system. Status information for

published applications may be obtained from either Private PAIR or Public PAIR.

Status information for unpublished applications is available through Private PAIR only.

For more information about the PAIR system, see http://pair-direct.uspto.gov. Should

you have questions on access to the Private PAIR system, contact the Electronic

Business Center (EBC) at 866-217-9197 (toll-free).

Edna Wong

Primary Examiner

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EW June 24, 2004